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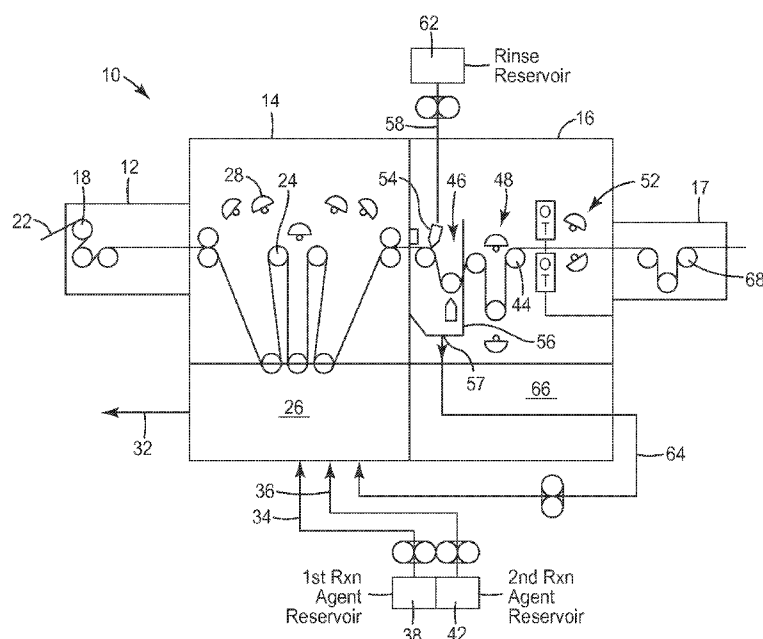
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Declarations under Rule 4.17:

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- as to the applicant's entitlement to claim the priority of the earlier application (Rule 4.17(iii))

[Continued on next page]

(54) Title: METHODS OF CONTINUOUSLY WET ETCHING A PATTERNED SUBSTRATE



(57) Abstract: A method for patterning a substrate. The method includes wet etching a metalized substrate within a reaction vessel by contacting the metalized surface with oxidizing and metal complexing agents to remove metal from an unpatterned region. The method further includes maintaining the concentrations of the oxidizing and metal complexing agents in an etchant bath by delivering a replenishment feed of each of the oxidizing and metal complexing agents to the etchant bath. The method further includes and maintaining the concentration of the metal in the etchant bath by discharging an amount of the etchant bath from the reaction vessel. The first and second replenishment feed rates and the etchant bath removal rate are determined based at least in part on a rate that metal etched from the substrate enters the etchant bath.

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